Created: 2006/02/20, Shong Yin	
1) Preliminary Measurements:	
Furnace Temperature:	
Control Wafer Sheet Resistance:	
2) Pre-Deposition:	
Time (sec)	
<b>Sheet Resistance</b>	
SOG Etch Time:	
Drive-In	
Time (sec)	
Anneal:	
Time (sec)	
<b>Sheet Resistance</b>	
3) Measurements after Process Completion: Intermediate Oxide Thickness (Nanospec):	
Questions (In preparation for Lab Report 1):  Calculate Theoretical Oxide Thickness using Deal-Grove Model	
Calculate Theoretical Onice Thickness using Dear Grove Wood!	

Calculate surface dopant concentration from the sheet resistance after pre-deposition and

EE143 Lab Week 7 Measurement Checklist:

drive-in.